

Sacrificial Surfactanated Pre-wet for Defect Reduction in a Semiconductor Photolithography Developing Process

Abstract of the Disclosure

A method and apparatus for developing a resist on a substrate in which a sacrificial surfactant-containing liquid is first applied to a resist as a pretreatment to reduce developing process defects and to improve the development process time and the uniformity of the resist. The pretreatment
5 is followed by supplying a developing solution to the resist and thereafter developing the resist.